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INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No. NMTC-0755 Serial No. 10/029,041
Applicant ZHANG, Youping
Filing Date 12/20/2001 Group 1756

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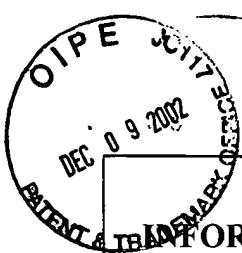
U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
	6,453,457 B1	9/17/2002	Pierrat, et al.	716	19	9/29/2000
	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.
	Cobb, N., et al., "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model", SPIE, Vol. 3051, pp. 458-468, March 12-14, 1997.
	Cobb, N., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing", Dissertation, University of California at Berkeley, UMI Microform 9902038 (139 pages).
	Toublan, O., et al., "Phase Aware Proximity Correction for Advanced Masks", SPIE, Vol. 4000, pp. 160-170, March 1-3, 2000.
	Anonymous, "Parameterization For Full Shape And Rule Dependent Dissection", IPCOM000009587D, September 4, 2002 (9 pages).

EXAMINER:

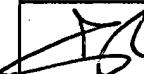
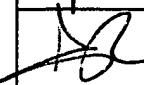
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	Filing Date 12/20/2001	Group 2812

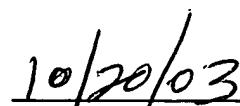
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION	RECEIVED JUL 22 2002 TC 1700
	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.	
	Lithas, "Lithas: Optical Proximity Correction Software" (2 pages).	
	Precim, "Proxima System", Precim Company, Portland, Oregon (2 pages).	
	Precim, "Proxima Wafer Proximity Correction System", Precim Company, Portland, Oregon (2 pages).	
	Rieger, M., et al., "Mask Fabrication Rules for Proximity-Corrected Patterns", Precim Company, Portland, Oregon (10 pages).	
	Rieger, M., et al., "Using Behavior Modeling for Proximity Correction", Precim Company, Portland, Oregon (6 pages).	
	Cobb, et al., "Fast Sparse Aerial Image Calculation for OPC", SPIE, Vol. 2621, pp. 534-544, September 20-22, 1995.	
	Lucas, K., et al., "Model Based OPC for 1st Generation 193nm Lithography", Motorola Inc., IDT assignee to IMEC (12 pages).	
	Sturman, J., et al., "Quantifying Proximity and Related Effects in Advanced Wafer Processes", Precim Company, Hewlett Packard Labs (9 pages).	
	Sugawara, M., et al., "Practical Evaluation of Optical Proximity Effect Correction by EDM Methodology", Sony Corporation (11 pages).	
	Saleh, B., et al., "Reduction of Errors of Microphotographic Reproductions by Optimal Corrections of Original Masks", Optical Engineering, Vol. 20, No. 5, pp. 781-784, September/October 1981.	
	Fu, C.C., et al., "Enhancement of Lithographic Patterns by Using Serif Features", IEEE, Transactions On Electron Devices, Vol. 38, No. 12, pp. 2599-2603, December 1991.	
	Harafuji, K., et al., "A Novel Hierarchical Approach for Proximity Effect Correction in Electron Beam Lithography", IEEE, Vol. 12, No. 10, pp. 1508-1514, October 1993.	
	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).	

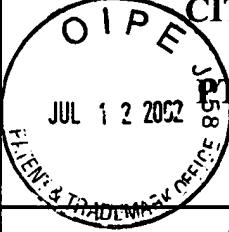
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JUL 22 2002
TC 1700

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
	Stirniman, J., et al., "Fast Proximity Correction with Zone Sampling", SPIE, Vol. 2197, pp. 294-301 (1994).
	Stirniman, J., et al., "Optimizing Proximity Correction for Wafer Fabrication Processes", SPIE, Photomask Technology And Management, Vol. 2322, pp. 239-246 (1994).
	Stirniman, J., et al., "Wafer Proximity Correction and Its Impact on Mask-Making", Busac News, Vol. 10, Issue 1, pp. 1, 3-7, 10-12, January 1994.
	Henderson, R., et al., "Optical Proximity Effect Correction: An Emerging Technology", Microlithography World, pp. 6-12 (1994).
	Barouch, E., et al., "OPTIMASK: An OPC Algorithm for Chrome and Phase-Shift Mask Design", SPIE, Vo. 2440, pp. 192-206, February 1995.
	Yen, A., et al., "Characterization and Correction of Optical Proximity Effects in Deep-Ultraviolet Lithography Using Behavior Modeling", J. Vac. Sci. Technol. B, Vol. 14, No. 6, pp. 4175-4178, November/December 1996.
	Morimoto, H., et al., "Next Generation Mask Strategy - Technologies are Ready for Mass Production of 256MDRAM?", SPIE, Vol. 3236, pp. 188-189 (1997).
	Park, C., et al., "An Automatic Gate CD Control for a Full Chip Scale SRAM Device", SPIE, Vol. 3236, pp. 350-357 (1997).
	Dolainsky, C., et al., "Application of a Simple Resist Model to Fast Optical Proximity Correction", SPIE, Vol. 3051, pp. 774-780 (1997).
	Chuang, H., et al., "Practical Applications of 2-D Optical Proximity Corrections for Enhanced Performance of 0.25um Random Logic Devices", IEEE, pp. 18.7.1-18.7.4, December 1997.
	Asai, N., et al., "Proposal for the Coma Aberration Dependent Overlay Error Compensation Technology", Jpn. J. Appl. Phys., Vol. 37, pp. 6718-6722 (1998).

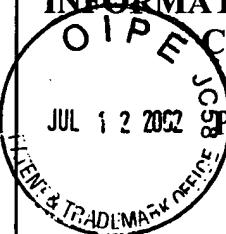
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
	5,825,647	10/20/1998	Tsudaka	364	167.03	3/12/1996
	5,991,006	11/23/0199	Tsudaka	355	53	10/27/1997
	6,081,658	6/27/2000	Rieger, et al.	395	500.22	12/31/1997
	6,289,499	9/11/2001	Rieger, et al.	716	21	1/7/2000
	6,243,855 B1	6/5/2001	Kobayashi, et al.	716	19	9/29/1998
	6,249,597 B1	6/19/2001	Tsudaka	382	144	12/17/1998

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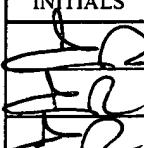
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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
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	GB 2,324,169 A	10/14/1998	GB	—	—	<input type="checkbox"/>	<input type="checkbox"/>

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